

Appl. No. 10/824,857  
Docket No. 2102487-991181  
Response to Office Action of April 28, 2005

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1-7. (Cancelled)

8. (Currently amended) A computer implemented layout design method, comprising:

- generating a first line having a first line width and extending in a predetermined direction;
- generating a second line having a second line width, extending in a direction different from said first line, and having its terminal end overlapping a terminal end of said first line;
- stretching said first line in a longitudinal direction thereof;
- stretching said second line in a longitudinal direction thereof by a length 1/2 times as long as the second line width;
- deleting a projection from the terminal end of said first line and the terminal end of said second line, the projection protruding from an overlapped area where the terminal end of said first line and the terminal end of said second line overlap; and
- setting a connection pattern having ~~a polygon~~ an octagon connecting said first and second lines at an intersection point of a longitudinal center line of said first line and a longitudinal center line of said second line.

9. (Original) The layout design method of claim 8, wherein said first and second lines are lines generated in different levels.

10. (Original) The layout design method of claim 8, wherein said first and second lines are lines generated in the same level.

Page 2 of 5

EM\7190608.1  
352003-991181

Appl. No. 10/824,857  
Docket No. 2102487-991181  
Response to Office Action of April 28, 2005

11. (Cancelled).
12. (Original) The layout design method of claim 11, wherein said first and second lines are lines generated in different levels.
13. (Original) The layout design method of claim 11, wherein said first and second lines are lines generated in the same level.
14. (Original) The layout design method of claim 8, wherein in said stretching said first line in the longitudinal direction thereof, said first line is stretched by a length  $1/2$  times as long as the line width of said second line.
15. (Original) The layout design method of claim 8, wherein in said stretching said second line in the longitudinal direction thereof, said second line is stretched by a length  $1/2$  times as long as the line width of said first line.
16. (Currently amended) A manufacturing method of a semiconductor integrated circuit, comprising:
- forming a first line extending in a predetermined direction on a semiconductor substrate;
  - forming a level interlayer insulating film on said first line;
  - forming a ~~polygen~~ an octagonal via hole penetrating through said level interlayer insulating film;
  - forming a connection conductive portion filling said ~~polygen~~ an octagonal via hole and connecting with said first line; and
  - forming a second line extending at an angle unperpendicularly relative to said first line and having a terminal end connected to said connection conductive portion.